1	Supporting Information for
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3	Dependence of Thermoelectric Effects in Molecular Junctions on the Topography of the
4	Bottom-Electrodes
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**S**1

# 13 S1. Synthesis.

Thiophenol (HS(Ph)<sub>1</sub>). We synthesized thiophenol according to a procedure reported in the 14 literature.<sup>1</sup> Bromobenzene (2.00 mL, 20.00 mmol), ethane-1, 2-dithiol (2.01 mL 24.00 mmol), 15 KOH (5.60 g, 100.00 mmol) and CuSO<sub>4</sub>·5H<sub>2</sub>O (0.16 g, 5 mol%), were heated at 120 °C in DMF 16 (50.00 mL) under N<sub>2</sub> for 24 hours. The mixture was extracted three times with  $CH_2Cl_2$  (3 × 100 17 mL), washed with brine  $(3 \times 100 \text{ mL})$  after cooling down to room temperature. The combined 18 organic phases were then dried over Na<sub>2</sub>SO<sub>4</sub>, filtered and concentrated under reduced pressure. 19 The product thiophenol (0.24 g, yield 11.0%) was then purified by column chromatography 20 21 (silica gel, CH<sub>2</sub>Cl<sub>2</sub>/petroleum ether = 1/2 v/v). 1H NMR (400 MHz, DMSO-d6)  $\delta$  7.56 – 7.49 22 (m, 2H), 7.39 (t, J = 7.7 Hz, 2H), 7.34 – 7.25 (m, 1H). HRMS (ESI<sup>+</sup>): m/z calc for  $C_6H_7S$ 23 [M+H]<sup>+</sup> 111.0268, found 111.0257.





26 Fig. S1. <sup>1</sup>H NMR spectrum for HS(Ph)<sub>1</sub> in DMSO.



28 Fig. S2. The HRMS spectrum of  $HS(Ph)_1$ .



4-Terphenylthiol (HS(Ph)<sub>3</sub>). We synthesized 4-Terphenylthiol by the same procedure of 30 31 HS(Ph)<sub>1</sub>.<sup>1</sup> 4-bromo-p-terphenyl (3.09, 10.00 mmol), ethane-1,2-dithiol (1.00 mL 12.00 mmol), 32 KOH (2.80 g, 50.00 mmol) and CuSO<sub>4</sub>·5H<sub>2</sub>O (0.08 g, 5 mol%), were heated at 120 °C in DMF (30.00 mL) under N<sub>2</sub> for 24 hours. The mixture was extracted three times with CH<sub>2</sub>Cl<sub>2</sub> (3 × 100 33 mL), washed with brine  $(3 \times 100 \text{ mL})$  after cooling down to room temperature. The combined 34 35 organic phases were then dried over Na<sub>2</sub>SO<sub>4</sub>, filtered and concentrated under reduced pressure. The product thiophenol (0.24 g, yield 9.0%) was then purified by column chromatography 36 37 (silica gel, CH<sub>2</sub>Cl<sub>2</sub>/petroleum ether = 1/2 v/v). <sup>1</sup>H NMR (400 MHz, Chloroform-*d*)  $\delta$  7.70 – 7.61 (m, 6H), 7.58 (d, J = 8.5 Hz, 2H), 7.46 (t, J = 7.6 Hz, 2H), 7.35 (d, J = 8.5 Hz, 3H). HRMS 38 (ESI<sup>+</sup>): m/z calc for  $C_{18}H_{15}S$  [M+H]<sup>+</sup> 263.089, found 263.089. 39



41 Fig. S3. <sup>1</sup>H NMR spectrum for HS(Ph)<sub>3</sub> in CDCl<sub>3</sub>.

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#### 46 S2. Sample preparations.

47 **Template-stripped Au surfaces (Au<sup>TS</sup>).** Au<sup>TS</sup> substrates were prepared following procedures 48 reported previously.<sup>2</sup> Briefly, we deposited a 200 nm thick Au (Au with a purity of 99.999% 49 from Dimu Materials, Inc (China)) film on clean Si (100) wafers with a native SiO<sub>2</sub> surface 50 layer by thermal deposition (KYKY-400, Zhongke Ke Yi, China) with the base pressure being 51  $2 \times 10^{-5}$  Pa and the evaporation rate was about 0.2 Å s<sup>-1</sup> for Au at the first 50 nm and then

52 increased to ~1 Å s<sup>-1</sup> for the rest 150 nm. The glass slides  $(1.5 \times 1.5 \text{ cm}^2)$  were ultrasonically 53 cleaned with acetone and then ethanol for 20 minutes, and the slides were blown to dryness in 54 a stream of N<sub>2</sub> gas. After we cleaned the glass slides by a plasma of air for 5 mins at a pressure 55 of 100 Pa, the glass slides were glued on the Au surfaces by photo-curable optical adhesive 56 (Norland, No. 61). A 100 Watt UV lamp was used to cure the optical adhesive for 1 hour at a 57 distance of 60 cm from the light source. The Au surface that had been in contact with the Si/SiO<sub>2</sub> 58 wafer was lift-off by a razor blade.

**Direct deposition of Au (Au<sup>DE</sup>).** As described before,<sup>3</sup> the thermal evaporator was applied to 59 deposit Au on the Si wafers under high vacuum ( $2 \times 10^{-5}$  mbar) and the deposition rate and film 60 61 thickness were two significant parameters to determine the surface roughness, and the receipt we used for i)  $Au^{DE1}$  (rms = 1.3 nm, a 5 nm layer of Cr at rate of 0.1 Å s<sup>-1</sup> followed by 200 nm 62 of Au at a rate of 1 Å s<sup>-1</sup>), ii) Au<sup>DE2</sup> (rms = 2.2 nm, a 20 nm layer of Cr at rate of 1 Å s<sup>-1</sup> followed 63 by 200 nm of Au at a rate of 5 Å s<sup>-1</sup>) and iii) Au<sup>DE3</sup> (rms = 3.2 nm, a 40 nm layer of Cr at rate 64 of 1 Å s<sup>-1</sup> followed by 400 nm of Au at a rate of 5 Å s<sup>-1</sup>). To eliminate surface contamination 65 from the ambient, the Au<sup>DE</sup> surfaces removing from the vacuum chamber were immediately 66 used to form SAMs. 67

68 **SAMs preparation.** All thiol terminated molecules except  $HS(Ph)_1$  and  $HS(Ph)_3$  were 69 purchased from Sigma Aldrich with their highest purity (at least >98%) that we can found. To 70 form SAMs, Au substrates were immersed in degassed 3 mM ethanolic solutions of  $HSC_m$  (m 71 = 4, 6, 8) and  $HS(Ph)_n$  (n = 1, 2, 3) over a period of time of 3 h under an inert nitrogen 72 environment. The SAMs were rinsed with ethanol (AR grade) to remove the physisorbed 73 molecules, dried in a stream of dry nitrogen gently and used for experiments within minutes to 74 avoid degradation of the S-Au bond and surface contaminations.

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- 76

#### 77 S3. Sample Characterizations.

Atomic Force Microscope (AFM). The AFM images were recorded by Bruker Dimension 79 FastScan AFM with tapping mode tips (Dimension, resonant frequency: 1.4 MHz, force 80 constant:  $18 \text{ N m}^{-1}$ ). We measured three  $1 \times 1 \mu \text{m}$  and three  $5 \times 5 \mu \text{m}$  images on three substrates 81 for each type of surfaces. The AFM software NanoScope Analysis (version 1.8) was used to 82 analyze the AFM images for topography and the rms roughness.

X-ray Photoelectron Spectroscopy (XPS) Measurements. XPS was used to characterize the 83 SAMs of HSC<sub>m</sub> and HS(Ph)<sub>n</sub> with instruments located in National Center of Electron 84 Spectroscopy in Beijing. The energy of the incident X-ray beam (1486.6 eV) was used with the 85 Thermo Scientific K-Alpha XPS system. We recorded the high-resolution XPS spectra of S 2p, 86 87 C 1s and Au 4f. In analysis, we used the least-square peak fit with a pseudo-Voigt function (a linear combination of Lorentzian (30%) and Gaussian (70%) functions)<sup>4</sup> to fit the XPS spectra 88 with Avantage software, and the sloping background was modelled using a smart background 89 correction. 90

91 The physical absorbed molecules with binding energy being about 161eV of S 2p spectrum<sup>5</sup> can be observed for  $HS(Ph)_n$  (n = 1, 2, 3) anchored on Au<sup>DE</sup> electrode with rms 92 roughness being 3.2nm (Fig. S24). In contrast, HSC<sub>m</sub>, based on S 2p spectrum (Fig. S26), were 93 relatively densely assembled without physical absorbed molecules on rough Au substrate, 94 indicating that the topography of bottom-electrode had more remarkable impacts on packing of 95 96 conjugated molecules, the explanations of which was that HS(Ph)<sub>n</sub> SAMs anchored on rough 97 bottom-electrode with extremely deteriorated packing and destroyed  $\pi - \pi$  interactions of  $HS(Ph)_n$  for their more rigid nature. 98

99 Ultraviolet Photoelectron Spectroscopy (UPS) Measurements. Work functions (WF) and
100 HOMO energy were detected by UPS function installed in the Thermo Scientific K-Alpha XPS
101 system. A specially designed biasing stage, which is in electrical contact with the analyzer, was

applied to hold the samples. All measurements were performed in an ultrahigh vacuum chamber with a base pressure of  $1 \times 10^{-8}$  pa. To probe the valence band, the photon energy at 21.22 eV was used and -10 V bias was applied to the sample to overcome the work function of the analyzer. All UPS spectra were referenced to the Fermi edge of Au.

106

## 107 **S4.** Electrical and thermoelectrical measurements.

Electrical Measurements and Analysis. We followed previously reported procedures <sup>2</sup> to 108 form the SAM-based junctions with cone-shaped tips of Ga<sub>2</sub>O<sub>3</sub>/EGaIn. The Au substrate was 109 grounded and the top-electrode was biased from  $0V \rightarrow 0.5 V \rightarrow 0V \rightarrow -0.5 V \rightarrow 0V$ , with a 110 111 step size of 50 mV, and a delay of 0.1 s, in all of our experiments. We measured three substrates to obtain  $\geq 20$  junctions, for each of which we collected 20-24 J(V) traces (that is a total of ~480 112 J(V) traces for each type of SAM). The J(V) data was analyzed following previously reported 113 procedures. <sup>6</sup> Briefly, we plotted the histogram of  $\log |J|$  for each bias and fitted Gaussians to 114 115 the histograms to obtain the log-mean ( $\mu_{log}$ ) of the values of J and their log standard-deviations 116  $(\sigma_{\log})$ .

Analysis of relationship between measured  $\Delta V$  and S. A polyimide (PI) film embedded with 117 heating resistors is used to heating the Au electrode to generate temperature difference 118  $(\Delta T = 0 \sim 8 \text{ K})$  across the junctions (Fig. 1a, b). Firstly, control experiments were performed on 119 clean Au surfaces with different surface roughness that were absent of molecules (Fig. S7, S9). 120 121 We supposed that the temperature difference was mainly distributed across EGaIn and tungsten tip (W tip) because the thermal conductivity of EGaIn  $(G_{th, EGaIn} \sim 26.43 \text{ W m}^{-1} \text{ K}^{-1})^7$  is far 122 123 overweight that of the surrounding air (~0.024 W m<sup>-1</sup> K<sup>-1</sup>). Wherein at Fig. S5, the difference between  $V_1$  and  $V_3$  represents the measured  $\Delta V$ ,  $T_1$  and  $T_3$  denote room temperature.  $V_2$  and  $T_2$ 124 125 are the potential and temperature measured by thermocouple of Au surface, respectively.

126 Therefore, the relationship between measured  $\Delta V$  and *S* for Au/EGaIn junctions can be generally 127 depicted as Equation. (S1-S4)

128 
$$S_{EGaIn} = -\frac{V_1 - V_2}{T_1 - T_2}$$
(S1)

129 
$$S_W = -\frac{V_3 - V_2}{T_1 - T_2}$$
(S2)

130 
$$V_1 - V_3 > 0, \ T_1 - T_2 < 0, \ S_{EGaln} - S_W > 0$$
 (S3)

131 
$$S_{EGaIn} - S_W = -\frac{V_1 - V_2 - V_2 + V_2}{T_1 - T_2} = -\frac{V_1 - V_3}{T_1 - T_2}$$
(S4)

Fig. S21-S22 shows plot of  $\Delta V$  as a function of  $\Delta T$  for Au/EGaIn junctions with different surface roughness. It can be found that the measured thermoelectric voltage is nearly independent with the surface roughness of bottom electrode, according to  $S = -\frac{\Delta V}{\Delta T}$ , and the obtained *S* is ~2.0 µV K<sup>-1</sup>. Considering the thermopower of W tip (*S<sub>W</sub>*) is 1.0 µV K<sup>-1</sup>,<sup>8</sup> and hence, the thermopower of EGaIn (*S<sub>EGaIn</sub>*) is 3.0 µV K<sup>-1</sup>.





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141 In the case of SAMs anchoring on Au electrode (Fig. S6), we defined  $T_1$ ,  $V_1$  and  $T_4$ ,  $V_4$  were the 142 temperature (room temperature) and potential of Syringe and W tip away from SAMs, 143 respectively.  $T_2$  and  $V_2$  were the temperature measured by thermocouple potential of Syringe 144 close to SAMs.  $V_3$  and  $T_3$  are the potential and temperature of Au surface. Theoretically, the 145 temperature gradient was supposed to locate across SAMs because the thermal conductivity of 146 n-alkanethiolates (~18 pW/K)<sup>9</sup> was 3 orders of magnitude smaller than that of EGaIn 147 ( $\Delta T_1 = (T_1 - T_2) \gg \Delta T_{2=} (T_2 - T_3)$ ), however, the measured  $T_2$  was higher than room temperature

148 and approximately half as  $T_3$  probably due to heat radiation ( $\Delta T = \Delta T_1 \approx \Delta T_{2=} \frac{1}{2} \Delta T_3 = (T_1 - T_3)$ ). 149 Hence, the relationship between measured  $\Delta V$  and *S* for Au/SAM//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions can 150 be generally depicted as Equation. (S5-S9)

151 
$$S_{EGaIn} = -\frac{V_1 - V_2}{T_1 - T_2} = -\frac{\Delta V_1}{\Delta T_1}$$
(S5)

152 
$$S_{SAM} = -\frac{V_2 - V_3}{T_2 - T_3} = -\frac{\Delta V_2}{\Delta T_2}$$
(S6)

153 
$$S_W = -\frac{V_4 - V_3}{T_4 - T_3} = -\frac{\Delta V_3}{\Delta T_3}$$
(S7)

154 
$$S_{EGaIn} + S_{SAM} - 2S_W = -\frac{V_1 - V_4}{\Delta T}$$
(S8)

155 
$$S_{SAM} = -\frac{V_1 - V_4}{\Delta T} - S_{EGaIn} + 2S_W = -\frac{V_1 - V_4}{\Delta T} - 1$$
(S9)



157 Fig. S6. Schematic diagram of the voltages and temperatures across Au/SAM//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junction.

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159 Thermopower of commercial silicon wafer. To verify that our platform can measure160 thermopower precisely, we measured the Seebeck effects of commercial silicon wafer by EGaIn

top-contacts, including P-type and N-type and the results are shown in Fig. S7-S8. It is evidence 161 162 that the thermoelectric voltage is positively-changed for P-type Si supporting holes transport once heating bottom electrode, and negatively-changed for N-type Si owing to charge transport 163 being dominated by electrons. The measured values of S for N-type and P-type Si are  $309.3 \pm$ 164 7.8  $\mu$ V K<sup>-1</sup> and -286.3  $\pm$  26.3  $\mu$ V K<sup>-1</sup>, respectively, similar to the reported values.<sup>10</sup> The sign 165 of S were determined by the nature of charge carriers with either electrons or holes. Fig. S8f 166 167 shows schematic diagram of thermoelectric test of Si, where a copper wire was attached to the 168 bottom surface of silicon wafer, ensuring that the carriers mainly migrate along the longitudinal 169 direction during test.



172 Fig. S7. Thermoelectric potential of Si//Ga<sub>2</sub>O<sub>3</sub>/EGaIn.173



174

175 **Fig. S8.** Thermoelectric potential of Cu//Si//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junction at different  $\Delta T$  for P-type Si (a) and N-type Si (b, d) corresponding histograms of  $\Delta V$  with a Gaussian fit to these histograms, (e) plot of  $\Delta V$  as a function of  $\Delta T$  for of N-type and P-type Si, (f) Schematic diagram of thermoelectric test of Si, where a copper wire was attached to the bottom surface of the wafer.

The measurement accuracy and error analyses for Seebeck coefficient. The accuracy of our thermal voltage measurement includes two parts: i) the accuracy of the output voltage and ii) the accuracy of the input temperature. Firstly, Fig. S9 shows the accurate voltage measurement was obtained by the voltmeter (2182A Nanovoltmeter, Keithley Inc., USA) with a detection limit of  $0.001\mu$ V. Considering the loss at the electrical circuit (mainly at the connection points), so we take the significant digit of the thermovoltage in this work as  $0.01\mu$ V.



187 Fig. S9. The voltmeter (2182A NANOVOLTMETER, KEITHLEY Inc., America) we utilized to measure
188 the voltage with accurate measurement of 0.001µV.

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190 Secondly, the input temperature was monitored by a thermal couple with a detection limit of 0.01K. Therefore, we estimate the accurate significant digit of temperature was 0.1K in this 191 study. Typical temperature-time trace is shown in Fig. S10. Wherein,  $T_1$  is the room 192 temperature, the average of  $T_1$  ( $< T_1 >$ ) and its standard deviation could be obtained over  $\sim 100$  s 193 test duration with a Gaussian fit. Once we heated the bottom-electrode,  $\Delta T$  occurred. When 194 195 reaching thermal equilibrium, the average of  $T_2$  ( $< T_2 >$ ) and its standard deviation could be obtained over ~200 s test time with a Gaussian fit. Then  $\Delta T$  was obtained by using  $\langle T_2 \rangle$ 196 subtracting  $< T_l >$ . We recorded at least 20 junctions to generate a histogram of  $\Delta T$  that can be 197 fitted with Gaussians to determine the mean value of  $\Delta T$  ( $\langle \Delta T \rangle$ ) and the corresponded standard-198 199 deviation, as shown in Fig. S10c. Hence, the error of  $\Delta T$  is 0.1K, accounting for ~2.5%. Since the error of S originated from  $\Delta V$  and  $\Delta T$ , that of the former  $(\sigma_{\Delta V})$  can be obtained from the 200 results of linear fitting in Fig. 3 and the latter ( $\sigma_{\Delta T}$ ) can be calculated from Fig. S10. 201



202

203 Fig. S10. (a) Temperature-time trace, (b) the related plot of  $\Delta T$  against number of junctions, (c) the 204 corresponded plot of histograms of  $\langle \Delta T \rangle$  (the mean value of  $\Delta T$ ) over 20 junctions with a Gaussian fit.

205 **Determination of power factor (PF).** We determined PF of  $HSC_m$  (m = 1, 2, 3) and  $HS(Ph)_n$ 206 (n = 1, 2, 3) according to a procedure reported in the literature.<sup>11</sup> The magnitude of electric field 207 intensity (*E*) can be given by:

 $E = \frac{V}{d} (GV m^{-1})$ (S10) 209 where V is the applied voltage and d is the molecular length considering the tilt angle (30°) of

210 SAMs. The conductivity ( $\sigma$ ) is the inverse of resistivity, and can be obtained as follows:

$$\sigma = \frac{J}{E} \left(\mu S \, cm^{-1}\right) \tag{S11}$$

212 J (A cm<sup>-2</sup>) is the current density. Using the calculated  $\sigma$  value and the measured *S*, the power 213 factor (PF) value was obtained according to the following relationship:

214 
$$PF = S^2 \sigma \left( \mu W K^{-2} m^{-1} \right)$$
(S12)

215 It can be found that, based on UPS characterization (Table S1-S7), the location of HOMO 216  $(E_{HOMO})$  and energy offset ( $\delta E$ ) were changed insignificantly for SAMs of HSC<sub>m</sub> and HS(Ph)<sub>n</sub> with similar l, indicating the coincidence of corresponded electronic structure. Then, S and G217 218 were lie on molecular length.  $HS(Ph)_1$  with the smaller l (Table S8), possessed higher G than that of HSC<sub>4</sub>, and theoretically larger PF. However, the physical absorbed molecules with 219 220 binding energy being ~161eV of S 2p spectrum can be observed for HS(Ph)<sub>1</sub> anchored on Au 221 electrode (Fig. S24). In contrast, HSC4, based on S 2p spectrum (Fig. S26), were relatively 222 densely assembled without physical absorbed molecules on Au<sup>TS</sup> substrate. And the more rigid nature of HS(Ph)<sub>1</sub> could deteriorate SAMs packing, leading to the reduced number of molecules 223 224 participating electron tunneling and lower S. In this case, the value of PF was dominated by S 225 for HS(Ph)<sub>1</sub> and HSC<sub>4</sub>. In contrast, the l of HS(Ph)<sub>2</sub> and HS(Ph)<sub>3</sub> were larger than that of HSC<sub>6</sub> and HSC<sub>8</sub>, respectively. In this case, PF of SAMs assembled on Au<sup>TS</sup> electrode was mainly 226 depended on G. Increased molecular length contributed to the enhanced electron tunneling 227 distance and decreased G and inferior PF. Therefore, we qualitatively explain, from the 228

229 perspective of electron tunneling and molecular packing, that the PF of  $HSC_m$  was larger than 230 that of similar molecular-length  $HS(Ph)_n$  by combining XPS and UPS result.



233 Fig. S11. The potential change of Au-S(Ph)<sub>2</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions for each spot with surface roughness 234 of Au electrode being 0.37 nm.



Fig. S12. The potential change of Au-S(Ph)<sub>2</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions for each spot with surface roughness of Au electrode being 1.30 nm.



Fig. S13. The potential change of Au-S(Ph)<sub>2</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions for each spot with surface roughness
 of Au electrode being 2.20 nm.

243



Fig. S14. The potential change of Au-S(Ph)<sub>2</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions for each spot with surface roughness of Au electrode being 3.20 nm.



248 249 Fig. S15. The potential change of Au-S(Ph)1//Ga2O3/EGaIn junctions for each spot with surface roughness 250 251 252 of Au electrode being (a) 0.37 nm, (b) 1.30 nm, (c) 2.20 nm and (d) 3.20 nm.





Fig. S17. The potential change of Au-SC<sub>4</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions for each spot with surface roughness of Au electrode being (a) 0.37 nm, (b) 1.30 nm, (c) 2.20 nm and (d) 3.20 nm.





 $J_{\text{Junction}}^{0}$   $J_{\text{Junction}}^{15}$   $J_{\text{Junction}}^{0}$   $J_{\text{Junction}}^{15}$   $J_{\text{Junction}}^{0}$   $J_{\text{Junction}}^{15}$   $J_{\text{Junction}}^{20}$  Fig. S19. The potential change of Au-SC<sub>8</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn junctions for each spot with surface roughness of Au electrode being (a) 0.37 nm, (b) 1.30 nm, (c) 2.20 nm and (d) 3.20 nm.



270 Fig. S20. The  $\Delta V$  at each applied  $\Delta T$  and the corresponding histograms of  $\Delta V$  with a Gaussian fit to these histograms of Au-S(Ph)<sub>n</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn and Au-C<sub>n</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn with different surface roughness, including rms 273 = 0.37 nm, rms = 1.30 nm, rms = 2.20 nm and rms = 3.20 nm.



Fig. S21. The potential change of Au/EGaIn junction for each spot with different surface roughness, (a) rms
= 0.37 nm, (b) rms = 1.30 nm, (c) rms = 2.20 nm and (d) rms = 3.20 nm.



275

**Fig. S22.** Plot of  $\Delta V$  as a function of  $\Delta T$  of Au/EGaIn junctions with different surface roughness. The solid lines are the linear fit.



**Fig. S23.** The histograms of  $\log_{10}$  *J* at -0.5V with Gaussian fits for Au- S(Ph)<sub>2</sub>//Ga<sub>2</sub>O<sub>3</sub>/EGaIn, where rms = 0.37 nm, 1.30 nm, 2.20 nm, 3.20 nm.



Fig. S24. The high resolution XPS S 2p spectra for Au-S(Ph)<sub>n</sub> (n = 1, 2, 3) with different surface roughness, including rms = 0.37 nm, 1.30 nm, 2.20 nm, 3.20 nm.



**Fig. S25.** The high resolution XPS C 1*s* spectra for Au-S(Ph)<sub>n</sub> (n = 1, 2, 3) with different surface roughness, including rms = 0.37 nm, 1.30 nm, 2.20 nm, 3.20 nm.



**Fig. S26.** The high resolution XPS S 2p spectra for Au-SC<sub>m</sub> (m = 4, 6, 8) with different surface roughness, including rms = 0.37 nm, 1.30 nm, 2.20 nm, 3.20 nm.



305 Fig. S27. The high resolution XPS C 1s spectra for Au-SC<sub>m</sub> (m = 4, 6, 8) with different surface roughness,

- 306 including rms = 0.37 nm, 1.30 nm, 2.20 nm, 3.20 nm.
- 307



308

309 Fig. S28. Ultraviolet photoemission spectroscopy (UPS) for bare Au with diverse rms.

Sample	$E_{\rm cutoff}({\rm eV})$	WF (eV)
rms=0.37 nm	16.61	4.61
rms=1.30 nm	16.63	4.59
rms=2.20 nm	16.50	4.72
rms=3.20 nm	16.70	4.52

311 Table S1. Properties of bare Au obtained by UPS.



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314 Fig. S29. Valence band and secondary cutoff spectra of the HOMO peak for Au-S(Ph)<sub>1</sub> measured by UPS.

315

**316** Table S2. Properties of Au-S(Ph)<sub>1</sub> SAMs obtained by UPS.

Sample	$\delta E ({ m eV})$	$E_{\rm cut  off} ({\rm eV})$	WF (eV)	$E_{\rm HOMO}({\rm eV})$
rms=0.37 nm	2.17	16.64	4.58	-6.75
rms=1.30 nm	2.18	16.50	4.72	-6.90
rms=2.20 nm	2.20	16.47	4.75	-6.95
rms=3.20 nm	2.20	16.73	4.49	-6.69



319 Fig. S30. Valence band and secondary cutoff spectra of the HOMO peak for Au-S(Ph)<sub>2</sub> measured by UPS.

318

321 Table S3. Properties of Au-S(Ph)<sub>2</sub> SAMs obtained by UPS.

Sample	$\delta E (\mathrm{eV})$	$E_{\rm cut  off}  (eV)$	WF (eV)	$E_{\rm HOMO} (\rm eV)$
rms=0.37 nm	2.14	17.40	3.82	-5.96
rms=1.30 nm	2.13	17.48	3.74	-5.87
rms=2.20 nm	2.34	17.66	3.56	-5.90
rms=3.20 nm	2.16	17.31	3.91	-6.07



324 Fig. S31. Valence band and secondary cutoff spectra of the HOMO peak for Au-S(Ph)<sub>3</sub> measured by UPS.325

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Sample		$\delta E ({ m eV})$	$E_{\rm cut  off} ({\rm eV})$	WF (eV)	$E_{\rm HOMO} ({\rm eV})$		
	rms=0.37 nm	2.15	16.72	4.50	-6.65		
	rms=1.30 nm	2.15	16.78	4.44	-6.59		
	rms=2.20 nm	2.19	16.82	4.40	-6.59		
	rms=3.20 nm	2.40	16.82	4.40	-6.80		

326 Table S4. Properties of Au-S(Ph)<sub>3</sub> SAMs obtained by UPS.



328

329 Fig. S32. Valence band and secondary cutoff spectra of the HOMO peak for Au-SC<sub>4</sub> measured by UPS.

Sample	$\delta E ({ m eV})$	$E_{\rm cut  off} ({\rm eV})$	WF (eV)	$E_{\rm HOMO}({\rm eV})$
 rms=0.37 nm	2.11	16.60	4.62	-6.73
rms=1.30 nm	2.21	16.63	4.59	-6.80
rms=2.20 nm	2.22	16.58	4.64	-6.86
 rms=3.20 nm	2.17	16.61	4.61	-6.78

**330** Table S5. Properties of Au-SC<sub>4</sub> SAMs obtained by UPS.



332

**333** Fig. S33. Valence band and secondary cutoff spectra of the HOMO peak for Au-SC<sub>6</sub> measured by UPS.

**334** Table S6. Properties of Au-SC<sub>6</sub> SAMs obtained by UPS.

Sample	$\delta E (\mathrm{eV})$	$E_{\rm cut  off}  (\rm eV)$	WF (eV)	$E_{\rm HOMO}({\rm eV})$
rms=0.37 nm	2.09	16.98	4.24	-6.33
rms=1.30 nm	2.17	16.91	4.31	-6.48
rms=2.20 nm	2.15	16.87	4.35	-6.50
rms=3.20 nm	2.24	17.06	4.16	-6.40



337 Fig. S34. Valence band and secondary cutoff spectra of the HOMO peak for Au-SC<sub>8</sub> measured by UPS.
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_	Sample	$\delta E ({ m eV})$	$E_{\rm cutoff}({\rm eV})$	WF (eV)	$E_{\rm HOMO} ({\rm eV})$		
_	rms=0.37 nm	2.17	16.96	4.26	-6.43		
	rms=1.30 nm	2.19	16.84	4.38	-6.55		
	rms=2.20 nm	2.20	16.71	4.51	-6.71		
	rms=3.20 nm	2.15	16.88	4.34	-6.49		
	rms=0.37 nm rms=1.30 nm rms=2.20 nm rms=3.20 nm	2.17 2.19 2.20 2.15	16.96 16.84 16.71 16.88	4.26 4.38 4.51 4.34	-6.43 -6.55 -6.71 -6.49		

339 Table S7. Properties of Au-SC<sub>8</sub> SAMs obtained by UPS.





342 Fig. S35. Plots of  $\log |J|$  at -0.50 V versus number of carbon atoms or aromatic rings for junctions

343 incorporating SAMs of (a)  $HSC_m$  (m = 4, 6, 8) and (b)  $HS(Ph)_n$  (n = 1, 2, 3). The solid lines are fits to the

344 Simmons Equation.



Fig. S36. The power factor as a function of surface roughness. *S*,  $\ln \sigma$  (at 0.1V) and PF as a function of rms roughness for HS(Ph)<sub>n</sub> (n = 1, 2, 3) and HSC<sub>m</sub> (m = 4, 6, 8). The dashed lines are a visual guide.

346

350 Table S8 Summary of molecular length (d) determined by ChemDraw software.

		$HS(Ph)_1$	HS(Ph) <sub>2</sub>	HS(Ph) <sub>3</sub>	HSC <sub>4</sub>	HSC <sub>6</sub>	HSC <sub>8</sub>
	l (Å)	4.59	8.72	12.92	5.27	7.82	10.37
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